

What is claimed is:

1. A polycrystalline MgO deposition material for a passivation layer of a plasma display panel, comprising:

a sintered pellet of a polycrystalline MgO, of which MgO
5 purity is more than 99.9% and relative density is more than 90%,
wherein a Si concentration in the polycrystalline MgO deposition
material is more than 30 ppm and less than 500 ppm.

2. The polycrystalline MgO deposition material of claim 1,
10 wherein the Si concentration in the polycrystalline MgO
deposition material is in a range of 220 ppm to 480 ppm.

3. The polycrystalline MgO deposition material of claim 1,
wherein the Si concentration in the polycrystalline MgO
15 deposition material is in a range of 250 ppm to 450 ppm.

4. The polycrystalline MgO deposition material of claim 1,
wherein the Si concentration in the polycrystalline MgO
deposition material is in a range of 280 ppm to 350 ppm.